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(71) Applicant (for all designated States except US): **ADVANCED TECHNOLOGY MATERIALS, INC.** [US/US]; 7 Commerce Crive, Danbury, CT 06810-4169 (US).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **OLANDER, W., Karl** [US/US]; 19616 Gulf Boulevard, #301, Indian Shores, FL 33785 (US). **MARGANSKI, Paul, J.** [US/US]; 8 Manners Avenue, Seymour, CT 06483 (US).

(74) Agent: **HULTQUIST, Steven, J.**; Intellectual Property Technology Law, PO Box 14329, Research Triangle Park, NC 27709 (US).

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(54) Title: VENTILATION GAS MANAGEMENT SYSTEMS AND PROCESSES

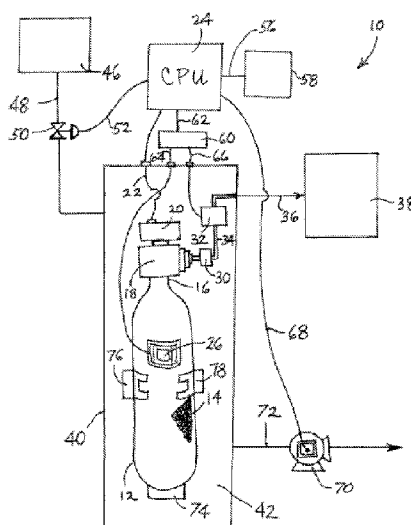


FIG. 1

(57) Abstract: A ventilation gas management system and process for an enclosure adapted to contain fluid supply vessel(s) and through which ventilation gas is flowed to provide safe operation in the event of leakage of fluid from a vessel. Ventilation gas flow is modulated to accommodate various hazard levels associated with the deployment and operation of such enclosure containing fluid supply vessel(s), e.g., a gas box or gas cabinet in a semiconductor manufacturing facility, thereby achieving reduction in ventilation gas requirements otherwise required for such deployment and operation.